| L Number | Hits | Search Text | DB | Time stamp |
|---|---|---|---|---|
| 5 | 12 | Hirae and controller and clean$4 | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/07/07 09:12 |
| 4 | 12 | Hirae and Sadao and Sato and Masanobu and Yasuda and Shuichi | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/07/07 09:12 |
| - | 0 | fushimi-ku.in. | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/06/22 10:07 |
| - | 0 | fushimiku.in. | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2002/09/03 14:02 |
| - | 2812 | fushimi.in. | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2002/09/03 14:02 |
| - | 1 | "fushimi-ku" and sadao and masanobu and yasuda | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2002/09/03 14:04 |
| - | 338139 | Hirae Sadao Sato Masanobu Yasuda Shuichi | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/12/11 15:14 |
| - | 1490 | (Hirae Sadao Sato Masanobu Yasuda Shuichi ) and ozone | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2002/09/03 14:06 |
| - | 237 | ((Hirae Sadao Sato Masanobu Yasuda Shuichi ) and ozone) and ultraviolet | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2002/09/03 14:06 |
| - | 93 | ((Hirae Sadao Sato Masanobu Yasuda Shuichi ) and ozone) and ultraviolet and clean$4 | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2002/09/03 14:07 |
| - | 27 | ((Hirae Sadao Sato Masanobu Yasuda Shuichi ) and ozone) and ultraviolet and clean$4 and wafer | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2002/09/03 14:13 |
| - | 0 | degendt and ultraviolet and ozone and clean$4 and wafer | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2002/09/03 14:14 |
| - | 3 | degendt | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2002/09/03 14:36 |
| - | 84151 | dainippon.as. | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2002/09/03 14:36 |

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|---|---|---|---|---|
| `-` | 16 | dainippon.as. and wafer and ozone and clean | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2002/09/06 09:44 |
| - | 0 | "242,4 nm" | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2002/09/06 08:33 |
| - | 8 | "242.4 nm" | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2002/09/06 08:33 |
| - | 0 | chapman near44 "1930" and ozone and nm | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2002/09/06 08:41 |
| - | 118 | chapman  and ozone and nm | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2002/09/06 08:41 |
| - | 53 | chapman  and ozone and nm and wavelength | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/03/03 13:54 |
| - | 19 | chapman  and ozone and nm and wavelength and clean | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2002/09/06 08:44 |
| - | 257 | wafer and ozone and nm and wavelength and clean | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2002/09/06 09:03 |
| - | 58 | wafer and ozone near12 UV and nm and wavelength and clean | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2002/09/06 09:04 |
| - | 16 | dainippon.as. and wafer and ozone and clean | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2002/09/06 13:43 |
| - | 2 | ("5288333").PN. | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2002/09/06 13:41 |
| - | 11 | (("5,975,098") or ("5,464,480") or ("6,403,498") or ("5,288,333") or ("20020088478")).PN. | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2002/09/06 13:43 |
| - | 5 | (("5,975,098") or ("5,464,480") or ("6,403,498") or ("5,288,333") or ("20020088478")).PN. | USPAT; US-PGPUB | 2002/09/06 13:43 |
| - | 3 | dainippon.as. and wafer and ozone and clean and UV | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2002/09/06 13:43 |

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| `,- ·` | 2 | ("5464480").PN. | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/03/03 13:55 |
| - | 0 | fushimi-ku.in. | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/12/11 15:13 |
| - | 0 | fushimi-ku.in. | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/12/11 15:14 |
| - | 377399 | Hirae Sadao Sato Masanobu Yasuda Shuichi | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/07/07 09:11 |
| - | 0 | "09751000" | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/12/12 07:12 |
| - | 1 | "09/751000" | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/12/12 07:12 |
| - | 54 | UV and (rotate spin) and substrate and (nozzle orifice) and 134/.ccls. | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/12/13 14:16 |
| - | 2 | "63-15710" | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/12/13 14:01 |
| - | 7 | "6315710" | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/12/13 14:01 |
| - | 0 | "6315710" and uv | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/12/13 14:02 |
| - | 0 | "6315710" and ultraviolet | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/12/13 14:02 |
| - | 0 | "6315710" and light | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/12/13 14:02 |
| - | 0 | "6315710" and wafer | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/12/13 14:02 |
| - | 79 | UV and (rotat$5 spin$4) and substrate and (nozzle orifice) and 134/.ccls. | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/12/13 14:17 |

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| ، - ، | 3 | photoresist near applicator and chuck and spin$4 | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/06/22 10:09 |
| – | 4 | photoresist near12 applicator and chuck and spin$4 | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/06/22 10:09 |
| – | 1713 | photoresist and chuck and spin$4 | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/06/22 10:10 |
| – | 513 | photoresist and chuck and spin$4 and ultraviolet | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/06/22 10:10 |
| – | 224 | photoresist and chuck near12 spin$4 and ultraviolet | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/06/22 10:35 |
| – | 1 | "4749440".PN. | USPAT | 2004/06/22 10:15 |
| – | 1 | "4765866".PN. | USPAT | 2004/06/22 10:15 |
| – | 1 | "4778532".PN. | USPAT | 2004/06/22 10:16 |
| – | 1 | "4778532".PN. | USPAT | 2004/06/22 10:16 |
| – | 1 | "4816098".PN. | USPAT | 2004/06/22 10:16 |
| – | 1 | "4904338".PN. | USPAT | 2004/06/22 10:17 |
| – | 1 | "4931103".PN. | USPAT | 2004/06/22 10:17 |
| – | 187 | chuck near12 spin$4 and (UV ultraviolet) and (dispens$4 coat$3) and nozzle | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/06/22 10:36 |
| – | 217 | chuck near12 spin$4 and (UV ultraviolet) and (dispens$4 coat$3) and nozzle | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/06/22 10:37 |
| – | 1 | "5626913".PN. | USPAT | 2004/06/22 10:44 |
| – | 1 | "5625433".PN. | USPAT | 2004/06/22 10:44 |
| – | 1 | "5252137".PN. | USPAT | 2004/06/22 10:44 |
| – | 1 | "4824763".PN. | USPAT | 2004/06/22 10:44 |
| – | 3 | "5910420" | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/06/23 11:23 |
| – | 4 | (("5464480") or ("6403498")).PN. | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/07/05 12:35 |
| – | 0 | controller near22 spin adj coat near33 (ultra$violet UV) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/07/07 06:49 |
| – | 0 | controller near22 spin adj coat near33 (cure ultra$violet UV) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/07/07 06:49 |
| – | 0 | controller near22 spin adj coat and (cure ultra$violet UV) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/07/07 06:50 |

| | | 1 | controller near22 spin adj coat | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB | 2004/07/07 06:50 |
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(1) "4816098".PN.
(1) "4904338".PN.
(1) "4931103".PN.
(187) chuck near12 spin$4 and
(217) chuck near12 spin$4 and
(1) "5626913".PN.
(1) "5625433".PN.
(1) "5252137".PN.
(1) "4824763".PN.
(3) "5910420"
(4) (("5464480") or ("6403498"
(0) controller near22 spin adj
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(1) controller near22 spin adj

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|---|---|---|---|---|---|---|---|---|---|---|
| 1 | ☐ | ☑ | US 20010001392 | 20010524 | 13 | Substrate treating method and apparatus | 134/1.3 | 156/345.11 ; | | Hirae, al. |
| 2 | ☐ | ☑ | US 4161356 A | 19790717 | 8 | Apparatus for in-situ processing of photoplat | 396/625 | 134/149; 134/153; | | Giffin, et al. |
| 3 | ☐ | ☑ | US 5078832 A | 19920107 | 22 | Method of treating wafer surface | 216/94 | 134/1; 134/3; | | Tanaka, |
| 4 | ☐ | ☑ | US 5288333 A | 19940222 | 25 | Wafer cleaning method and apparatus therefore | 134/31 | 134/11; 134/12; | | Tanaka, al. |
| 5 | ☐ | ☑ | US 5634980 A | 19970603 | 11 | Method for washing substrates | 134/3 | 134/18; 134/33; | 134/18 ; 134/ | Tomita, al. |
| 6 | ☐ | ☑ | US 5669979 A | 19970923 | 41 | Photoreactive surface processing | 134/1 | 134/1.1; 134/1.2; | 134/1; 134/1. | Elliott et al. |
| 7 | ☐ | ☐ | US 5843527 A | 19981201 | 60 | Coating solution applying method and app | 427/240 | 427/385.5; 438/782 | | Sanada, |
| 8 | ☐ | ☑ | US 5966635 A | 19991012 | 9 | Method for reducing particles on a substrat | | 134/104.1; 134/153; | | Hiatt, al. |
| 9 | ☐ | ☑ | US 5975098 A | 19991102 | 37 | Apparatus for and method of cleaning subs | 134/148 | 134/153; 134/181; | | Yoshita Mitsuak |
| 10 | ☐ | ☑ | US 6491452 B2 | 20021210 | 10 | Developing method and developing apparatus | 396/611 | 118/52; 427/240 | | Konishi al. |

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